

● Research for ALD

Beneq TFS 200



OVERVIEW



The Beneq TFS 200 is our most installed and trusted research tool in academic and corporate R&D. The TFS 200 has a myriad of upgrades and configurations available to fit your specific lab or application needs, making this a flexible ALD research platform that will grow with you.

FEATURES

Customizable

Work with our experts to find the right configuration for your lab environment. Choose from a number of options including direct/remote plasma, small batch chambers, and ranges of gas lines and sources.

Integratable

The TFS 200 is easy to integrate into existing production lines or cluster tools and can be equipped with auxiliary tools, like a glove box or load lock, for added versatility and automation.

Trusted

Over 250 TFS 200 tools are currently in operation at nearly 150 universities and institutes, resulting in hundreds of published articles and countless impactful results.

Application examples

- Al_2O_3 ALD on barrier applications
- HfO_2 , SiO_2 and SiN ALD on semiconductor applications
- SnO ALD for photovoltaic cells
- TiN and NbN ALD for superconductor applications

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SPECIFICATIONS	Process type	Thermal ALD, Plasma-enhanced ALD
	Usage	Research & Development, Production
	Integration	Stand-alone, Cluster, Glovebox, Loadlock
	Dimensions (L x W x H)	1325 x 600 x 1298 mm
	Temperature range	25–500 °C
	Substrate type	Up to 200 mm round wafers Up to 200 x 200 mm square wafers Wafer batch 3D parts Particles Porous and high aspect ratio structures

RESEARCH EQUIPMENT

Beneq maintains the largest install base of ALD research equipment for academic research and corporate R&D. We are dedicated to providing customers with premium, versatile research equipment to meet demanding lab environments and enable cutting-edge results.



Beneq TFS 500
The ultimate thin film system for ALD research and batch production.